(12) PATENT APPLICATION PUBLICATION

(19) INDIA

(21) Application No.2028/MUM/2012 A

(22) Date of filing of Application :13/07/2012

(43) Publication Date: 31/08/2012

## (54) Title of the invention: CHEMICAL BATH DEPOSITION EQUIPMENT

<ul> <li>(51) International classification</li> <li>(31) Priority Document No</li> <li>(32) Priority Date</li> <li>(33) Name of priority country</li> <li>(86) International Application No Filing Date</li> <li>(87) International Publication No</li> <li>(61) Patent of Addition to Application Number Filing Date</li> </ul>	:C25D 19/00 :NA :NA :NA :NA :NA :NA :NA	(71)Name of Applicant:  1)BETKAR MAHESHWAR MALLIKARJUN Address of Applicant: SHIVAI, GOKUNDA, TQ.KINWAT, DIST. NANDED, MS, INDIA, PIN_431811. Maharashtra India (72)Name of Inventor: 1)BETKAR MAHESHWAR MALLIKARJUN
. ,	:NA	
(62) Divisional to Application Number	:NA	
Filing Date	:NA	

## (57) Abstract:

The present invention concerns chemical bath deposition equipment for depositing the thin films and method thereof. The deposition method implemented by the invented equipment is advantageous in that, the integrated embodiment bi-directional DC motor successfully optimizes the thermal field distribution and flow field distribution inside the chemical bath reaction fluid, which improves the quality of thin films synthesized. The multiple substrate design enhances the quantity, hence less consumption of experimental compound solutions. The reaction ambience inside the housing is well isolated from the outside atmosphere for creating the toxic free surrounding.

No. of Pages: 25 No. of Claims: 10